

Fluoropolymer

NEOFLON PFA AP-211SH

TECHNICAL DATASHEET

NEOFLON PFA AP-211SH is a fully fluorinated high purity PFA. Melt flowability and stress crack resistance are excellent. It is suitable for injection molded parts used for semiconductors.

Introduction

- AP-211SH is a copolymer of tetrafluoroethylene and perfluoro alkyl vinyl ether. At the same time, it is a high purity PFA with its end groups completely fluorinated.
- Good melt flowability while maintaining excellent properties of PTFE. It can be used for melt molding as a thermoplastic resin. Injection molding and extrusion molding are suitable.
- Excellent in melt flowability. Applicable for injection molded products. It has been used for injection molded parts for semiconductors such as fitting nuts.
- Less eluted fluoride ions. Due to the fluorinated terminal group.
- The most excellent stress crack resistance in injection molding grade of PFA.
- **Excellent chemical resistance** which is not affected by most of the chemicals.
- Flexible and tough under the cryogenic to high temperature.
- Excellent heat resistance. Continuous use temperature is 260 °C.
- Nonflammable like POLYFLON PTFE and NEOFLON FEP.
- **Excellent weather resistance.** No properties change even when exposed outside for a long time.

Item	Unit	Value	Test Method
MFR	g/10min	14	ASTM D 3307 Compliant
Melting Point	°C	303	DSC
Specific Gravity	-	2.14	ASTM D 792 Compliant
Tensile Strength	MPa	35	ASTM D 1708 Compliant
Elongation	%	410	ASTM D 1708 Compliant

General physical properties

* The above values are representative values, not guaranteed values.

Handling method / Safety information

- Be sure to read the notes on SDS and labels before use.
- This product is intended for general industry, and therefore its adequacy and safety as a raw material for medical purposes cannot be guaranteed.



Packing specification 25Kg

For more information, visit our website.

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